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Research paper

Zero-mode waveguide detection of DNA translocation through FIB-organised arrays of engineered nanopores



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ABSTRACT

Zero-mode waveguides (ZMWs) are optical nanostructures fabricated in a thin metallic film capable of confining the excitation volume to the zeptoliter range.

In this work we describe the batch fabrication of a nanopore-based device, based upon high-resolution arrays of nanopores (of various sizes), which is used to directly measure the passage of DNA. In our method, nanopores are fabricated in ultrathin dielectric films with a deposited gold layer. The gold layer on the device induces a zero-mode waveguide illumination at the *cis* end of the nanopores.

The method presented allows for optical detection, in real time, at the level of a single molecule and a single pore. The detection of fluorescently labelled single molecules passing through the pores, measured using an electron multiplying charge coupled device camera, is described. Molecules inside the nanopore were invisible until they reached the volume illuminated by the evanescent field.

This fabrication methodology appears to be very promising for the development and batch fabrication of a new generation of nanopore-based sensor devices.

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1. Introduction

Nanopores have been shown to be very efficient devices to detect [1], characterise [2–4] and even sequence macromolecules such as DNA [5]. Most of the studies in the field are based on electrical driving and sensing of translocation events. Recent studies have demonstrated the possibility of using fluorescence and optical detection as an alternative [6–11] to follow the translocation of nucleic acids in solid state nanopores. Electrical and optical events have been shown to correlate precisely in time [12–14]. The major advantage of optical detection is the ability to achieve high parallelisation and specific labelling of the translocated molecules. In this article, we develop a methodology for the high throughput production of optical devices based upon Zero-Mode Waveguides coupled with nanopores.

A zero-mode waveguide (ZMW) is an optical waveguide that directs light energy into a volume (well) that is smaller, in all dimensions, than the wavelength of the illuminating light. ZWMs were originally fabricated in thin metallic films and were designed as electromagnetical attenuators [15]. More recently, pioneering work by Levene and coworkers [16] has shown that ZMWs can be used to isolate and then optically detect individual molecules that diffuse into nanowells. This is due to the

* Corresponding author. *E-mail address:* jacques.gierak@lpn.cnrs.fr (J. Gierak). fact that each well in the ZMW confines the illuminated volume (at the bottom of the well) to a few zeptoliters. ZMWs have potential as single molecule real time sequencing (SMRT) devices for sequencing DNA (reviewed in [17]). The entry of analyte molecules into the wells of a ZMW is a diffusion-limited process thus occupancy of individual wells is low. Furthermore, the entry and retention of different sized molecules is biased. For example, short DNA molecules are more likely to enter (or less likely to escape) than long molecules. In addition the molecule under analysis then needs to be trapped within the illuminated volume (the evanescent field region) at the bottom of the well in order to be detected or analysed (discussed in [18–20]).

Nanopore-ZMWs (NZMWs) have been introduced relatively recently. A NZMW contains a nanopore in the base of the ZMW well (in the evanescent field region). This allows for reversible electrophoretic focusing of biomolecules when a potential difference is applied across the device. Such NZMWs have been used to trap DNA in individual waveguides to enhance the sensitivity and efficiency of SMRT [18,19].

We have previously used a simple NZMW structure to optically detect translocated particles driven by a pressure gradient [21]. Here this work is expanded upon to demonstrate translocation driven by an applied potential difference. Furthermore, we show that these simple NZMW structures can be fabricated in a high throughput batch process using a gallium focused ion beam (FIB) to fabricate arrays of nanopores within the device. We have used this FIB process to produce NZMWs in



gold-coated silicon nitride (SiN) and silicon carbide (SiC). Nanopores of various sizes were produced within these substrates and optical detection of fluorescently labelled DNA molecules was demonstrated. We used nanopores of different sizes to study the relationship between frequency of translocation events and applied voltages and to show how critical voltage evolves with pore diameter.

The methodology demonstrated here is very well suited to the highthroughput batch production of a new generation of nanopore-based sensor devices.

2. Materials and methods

2.1. FIB setup - nanowriter, source and optics

For the nanopore fabrication a high resolution Ga + FIB Nanowriter developed in our laboratory [22] was used. The Nanowriter is based upon a single beam architecture working in conjunction with a laser interferometer controlled stage and patterning engines from Raith GmbH (Germany; http://www.raith.com). In this machine a specific gallium ion emitter device and controls are used. These allow for record onaxis angular intensity (up to 80μ A/str), a long lifetime and very long-term stability that are important parameters for dose control and precise placement of patterned features. The design of the ion optics includes a µm-sized beam-defining aperture at the entrance of the ion optics and two lenses operated to achieve, as routine, sub-10 nm resolution and abrupt current probe distribution profiles. This instrument combines the advantages of a very high resolution FIB system with the accuracy of a high precision laser interferometer stage (2 nm steps) and a high speed (10 MHz) digital pattern generator.

2.2. Membrane containing devices

Two different membrane materials, SiC (Home made in our facility) and Si3N4 (Norcada, Canada; http://www.norcada.com) were tested. In both cases two inch Si-based samples (300 µm thick) were fabricated using a GDSII mask design. Free standing membranes, 50 nm thick, were then covered with a 50 nm thick gold metal film evaporated using a x-low deposition speed to allow grain sizes in the range of a few nm. The sample was first covered with a thin layer of titanium (2 nm) as an adhesion layer and then with gold. Both metals were evaporated using an Plassys MEB550 electron gun machine at low speed

(0,2 nm/s for Ti and 0,5 nm/s for Au). After preparation, the samples were loaded into the FIB system. To avoid charge accumulation, a good electrical contact was maintained between the surface gold layer and the sample holder.

2.3. Device fabrication/patterning – navigation, dose – size calibration, processing and characterisation (TEM, SEM)

Precise patterning and automation were required in order to achieve optimum patterning results over the full wafer (~400 membranes). Automated step and repeat writing on each $50 \times 50 \mu m$ free-standing membranes was controlled by editing a position list (task list) based on calibration test results obtained either directly inside the FIB nanowriter using Scanning Ion Microscopy images (SIM) of the nanopores or externally via SEM, TEM or AFM.

Step 1: Sample containing free-standing membranes is loaded with the etched backside of the wafer facing the incoming ion beam. In this orientation, the edges of each membrane can be detected and used as an alignment feature.

Step 2: A classical 3 point (X, Y, θ) alignment procedure is then used for allowing automated navigation.

Step 3: On a sacrificial set of membranes, a dose calibration array is patterned and then inspected via ion or electron microscopy. For electron microscopy, the sample has to be unloaded from the FIB.

Step 4: Once the optimum ion dose and patterning conditions have been selected and validated, the complete wafer is automatically patterned. Each membrane is drilled with a matrix of 5×5 nanopores.

Typical dwell times for the pore size fabrication were found to be in the order of 20-40 ms (Ga + ion, 30 keV, 5-8 pA). The total time for the wafer processing is in the order of 1 h (field alignment and stage displacements/positioning).

Unattended batch processing is desirable to allow for maximum efficiency of system usage with the highest job yield and minimum feature variation.

2.4. Translocation assay. Details of microscope setup, lambda DNA and YOYO labelling

Phage lambda DNA molecules (New England Biolabs, USA) were labelled using a fluorescent intercalating dye (YOYO-1; Thermo Fisher Scientific, USA).



Fig. 1. Experimental setup for the detection of translocation of labelled DNA molecules. Illuminating light is shown in green. Emitted light (fluorescence) is shown in red. In a Zero-Mode Waveguide the fluorescence emission is restrained to the vicinity of the nanopore. DNA molecules are pulled through the nanopore with an electrical field. Translocation events are detected by local fluorescence emission during exit of the molecules. (For interpretation of the references to color in this figure legend, the reader is referred to the web version of this article.)

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